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STATEMENT BY APPLICANT			LICANI	First Named Inventor	Christopher Hamlin
				Group Art Unit	2825
				Examiner Name	S. Whitmore
Sheet	1 .	of	1	Attorney Docket No.	/ 03-2099
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PAGE 5/5 * RCVD AT 5/10/2005 5:08:52 PM [Eastern Daylight Time] * SVR:USPTO-EFXRF-1/7 * DNIS:8729306 * CSID:408 433 7460 * DURATION (mm-ss):01-34

In Place of FORM PTO-1449 (Modified)

Scrial No.:

Applicant:

Christopher Hamlin, et al.

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STATEMENT

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